

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	9	(ion\$1 adj30 (dop\$5 or implant\$9)) and (plasma adj30 (chamber\$1 or hous\$5)) and ((platen or support\$5) adj30 (wafer\$1 or substrate\$1 or semiconduct\$5 or workpiece\$1)) and gas\$3 and (plasma adj20 sheath) and (positive adj20 ion\$1) and ((faraday or dosimet\$5) adj20 cup\$1) and ((collect\$5 or detect\$5 or sens\$5) adj30 positive adj30 ion\$1)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2008/02/03 16:36
2	BRS	L2	5	((ion\$1 adj30 (dop\$5 or implant\$9)) and (plasma adj30 (chamber\$1 or hous\$5)) and ((platen or support\$5) adj30 (wafer\$1 or substrate\$1 or semiconduct\$5 or workpiece\$1)) and gas\$3 and (plasma adj20 sheath) and (positive adj20 ion\$1) and ((faraday or dosimet\$5) adj20 cup\$1) and ((collect\$5 or detect\$5 or sens\$5) adj30 positive adj30 ion\$1)).clm.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2008/02/03 16:40
3	BRS	L3	55	(ion\$1 adj30 (dop\$5 or implant\$9)) and (plasma adj30 (chamber\$1 or hous\$5)) and ((platen or support\$5) adj30 (wafer\$1 or substrate\$1 or semiconduct\$5 or workpiece\$1)) and puls\$5 and ((faraday or dosimet\$5) adj20 cup\$1)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2008/02/03 16:52

	Type	L #	Hits	Search Text	DBs	Time Stamp
4	BRS	L4	7	((ion\$1 adj30 (dop\$5 or implant\$9)) and (plasma adj30 (chamber\$1 or hous\$5)) and ((platen or support\$5) adj30 (wafer\$1 or substrate\$1 or semiconduct\$5 or workpiece\$1)) and puls\$5 and ((faraday or dosimet\$5) adj20 cup\$1)).clm.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2008/02/03 17:26